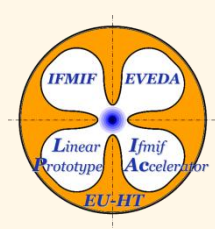


Challenges for the LIPAc Ionization Profile Monitor (IPM)

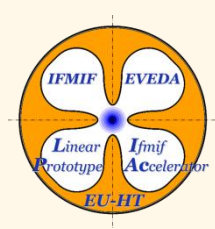
Jan Egberts^{1,2,3}, Philippe Abbon¹, Hervé Deschamps¹, Fabien Jeanneau¹, Jacques Marroncle¹, Jean-Philippe Mols¹, Thomas Papaevangelou¹,

1) CEA Saclay 2) École Doctorale MIPEGE, Université Paris Sud XI 3) Ditanet, FP7, Marie Curie



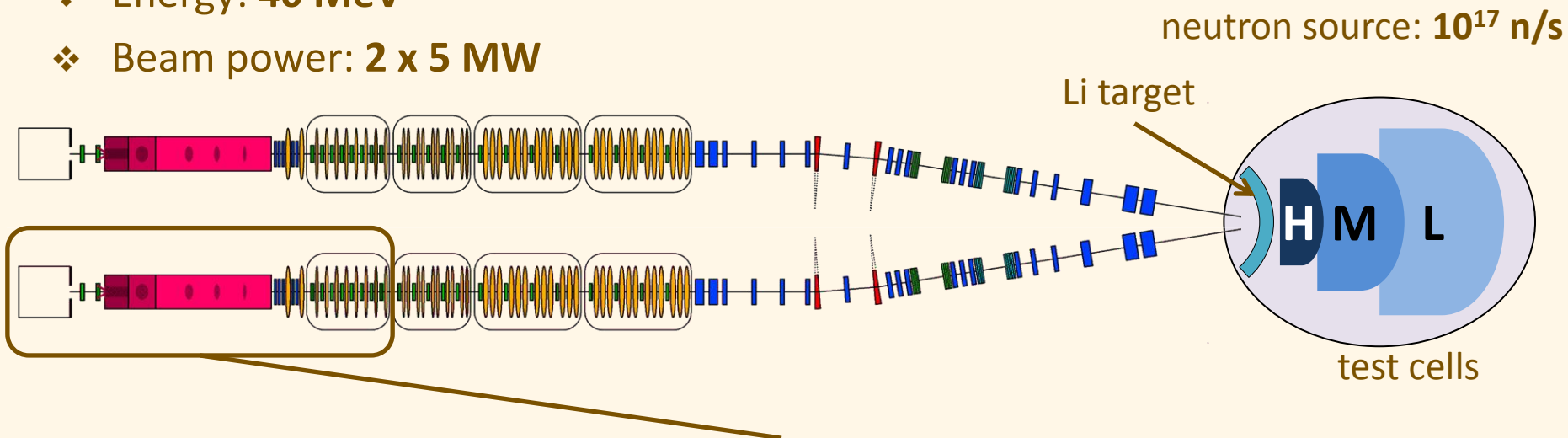
Outline

- ❖ LIPAc Accelerator (IFMIF - EVEDA)
- ❖ IPM – Characteristics
- ❖ Challenges
 - ❖ Background Radiation
 - ❖ High Beam Current
- ❖ Conclusion



IFMIF: International Fusion Material Irradiation Facility

- ❖ Beam current: **2 x 125 mA** cw deuterium
- ❖ Energy: **40 MeV**
- ❖ Beam power: **2 x 5 MW**



LIPAc: Linear IFMIF Prototype Accelerator

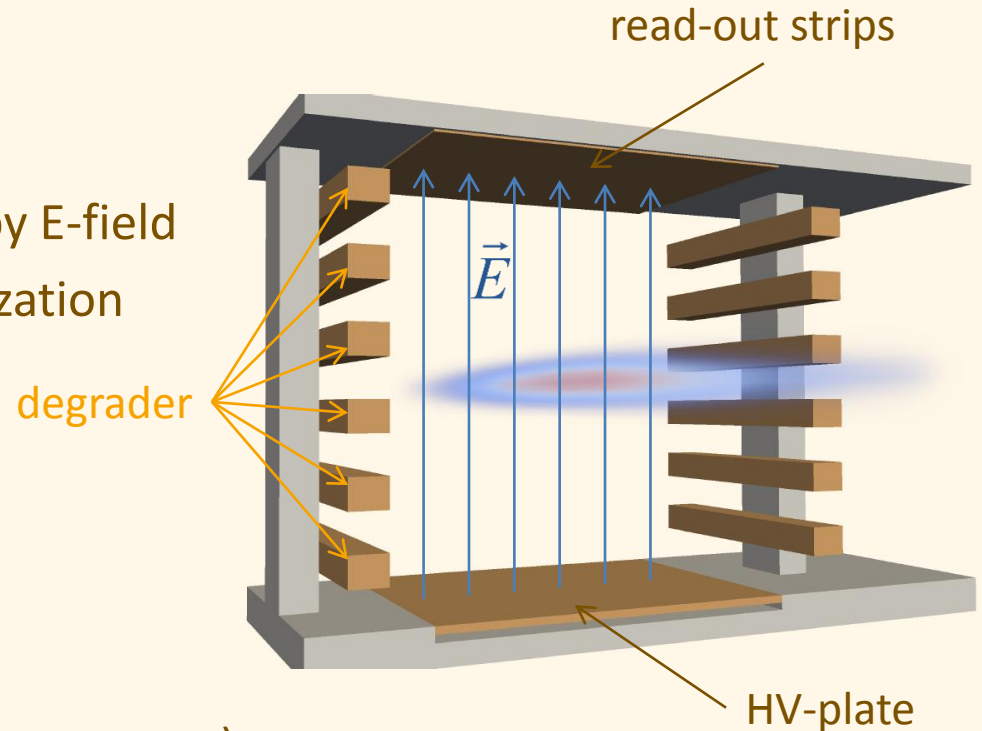
Prototype limited to **1 x 125 mA** cw @ **9 MeV, 1.125 MW**

Principle of Operation:

- ❖ Beam ionizes residual gas
- ❖ Electrons / ions are extracted by E-field
- ❖ Beam profile derived from ionization current

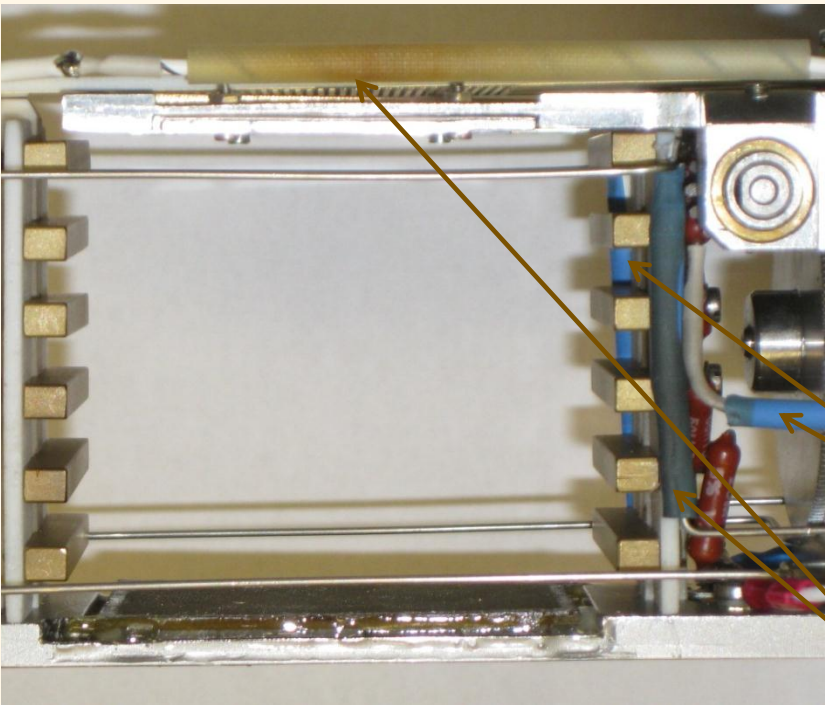
LIPAc Challenges:

- ❖ Limited space
⇒ Compact design (wrt. large aperture)
- ❖ High background radiation (~7 kSv/h close to the beam dump)



Mainly radiation hard materials used, like:

metals, ceramics, epoxy glass, indium joints...

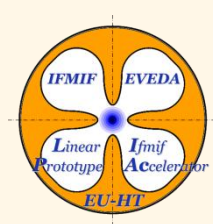


For radiation weak materials:

- ❖ Front-end electronics at remote distance and shielded
- ❖ Resistors are well shielded
- ❖ Flat resistors used to minimize irradiation

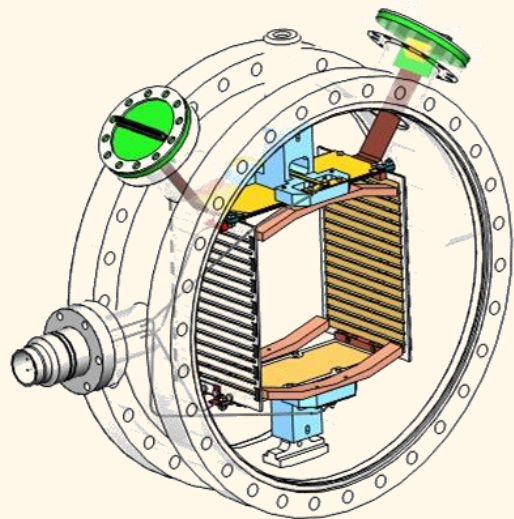
Virtually no radiation effects on plastics that were shielded by the beam pipe / the IPM

Strong radiation effects on plastics of the IPM prototype after tests at GSI



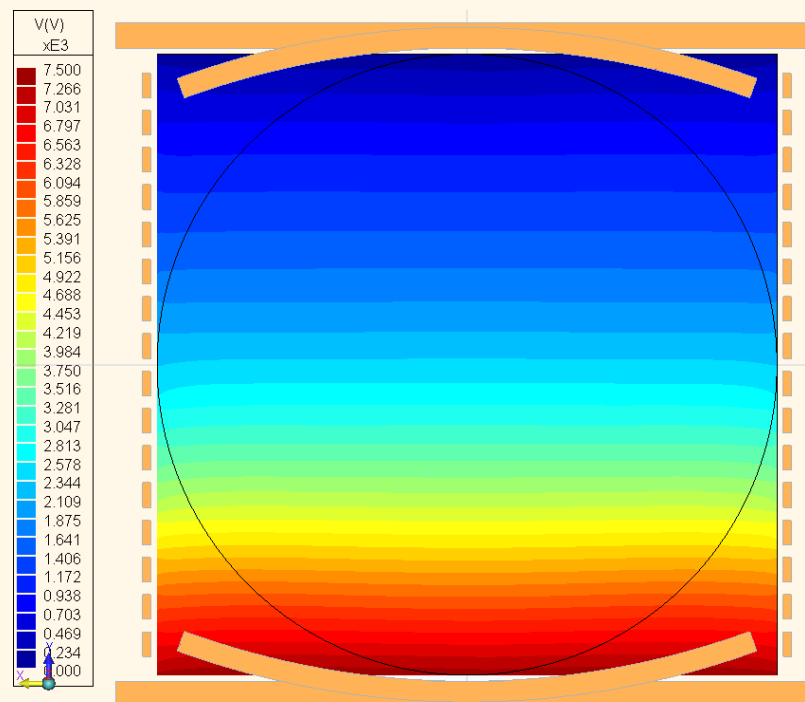
Final Design Challenges:

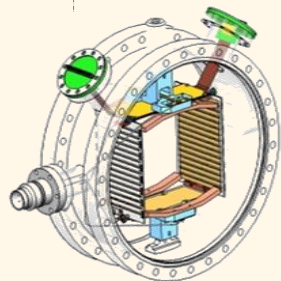
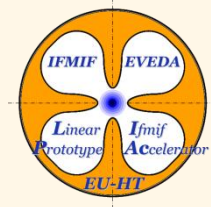
- ❖ Lack of space \Rightarrow very compact design required
- ❖ High radiation level \Rightarrow radiation hard components exclusively
- ❖ Large aperture of 150 mm



Design results:

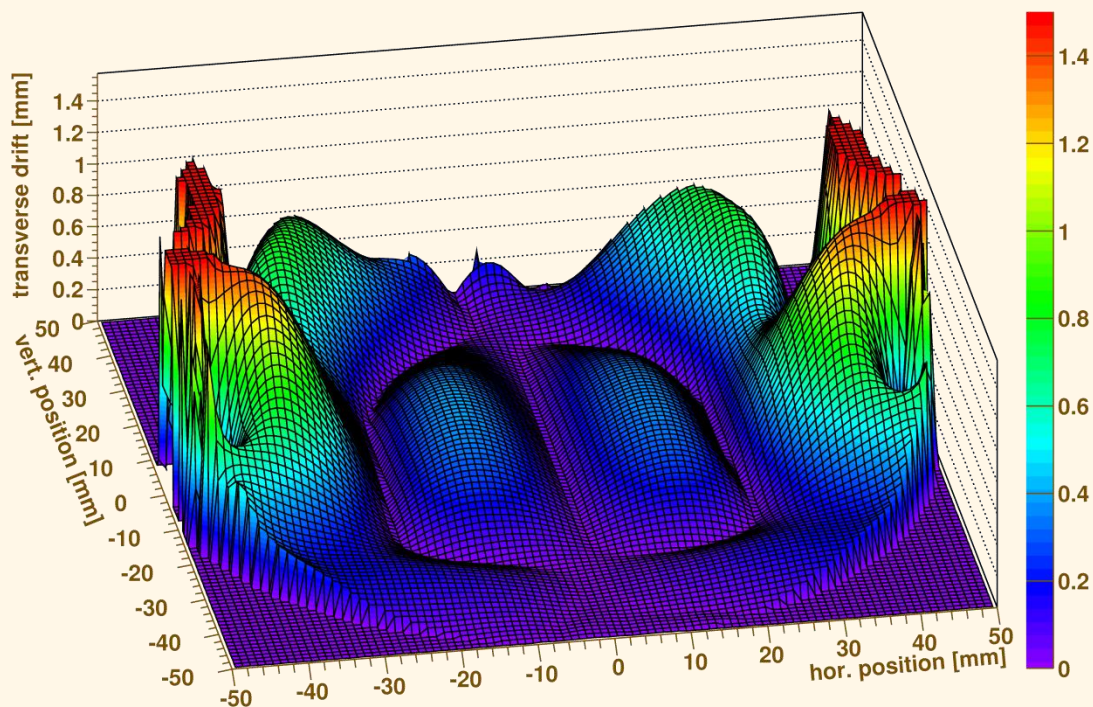
- ❖ Depth of 100 mm with an aperture of 150 mm
- ❖ E-field uniform within $\sim 3\%$





Neglecting Space Charge Effect!

Simulation of the Transverse Ion Drift in the el. Field

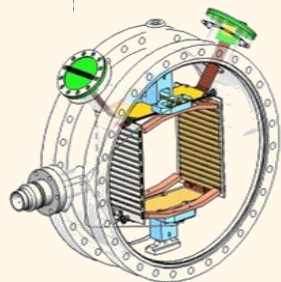
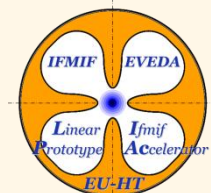


Particle Tracking:

Transverse displacement during ion drift versus starting position

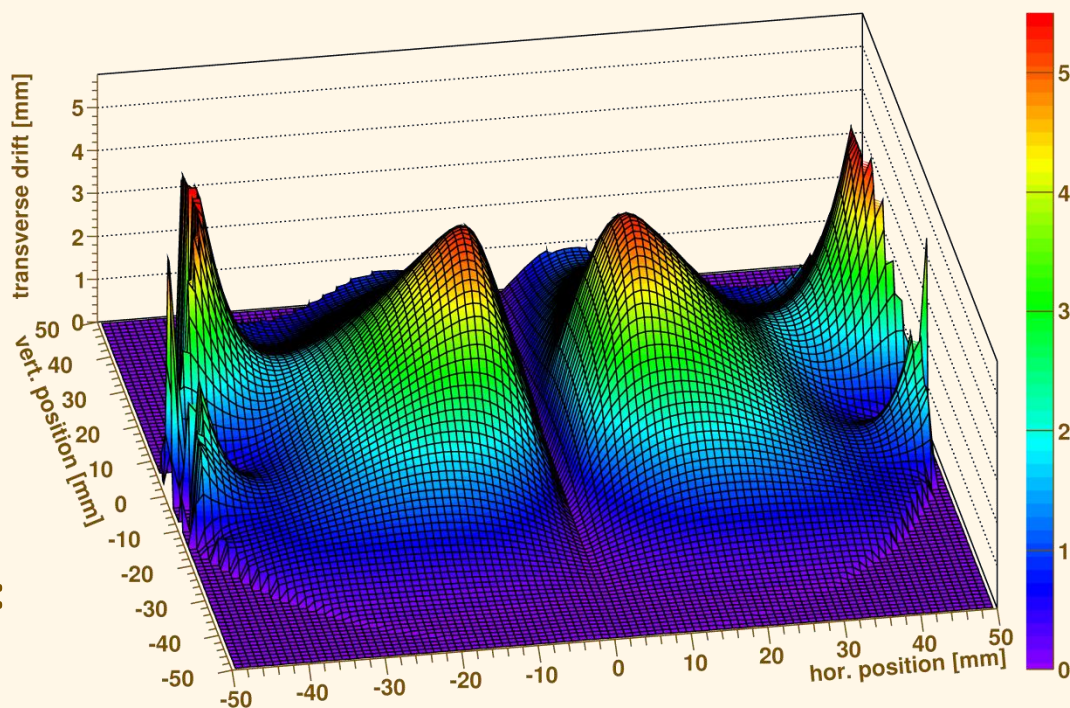
In beam region:

Displacement < 500 μm



Space Charge for 125 mA Beam

Transverse Ion Drift with a Beam of 125 mA

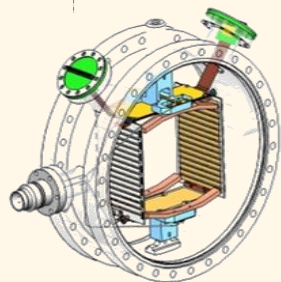
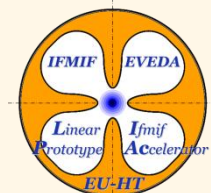


Particle Tracking:

Transverse displacement during ion drift versus starting position

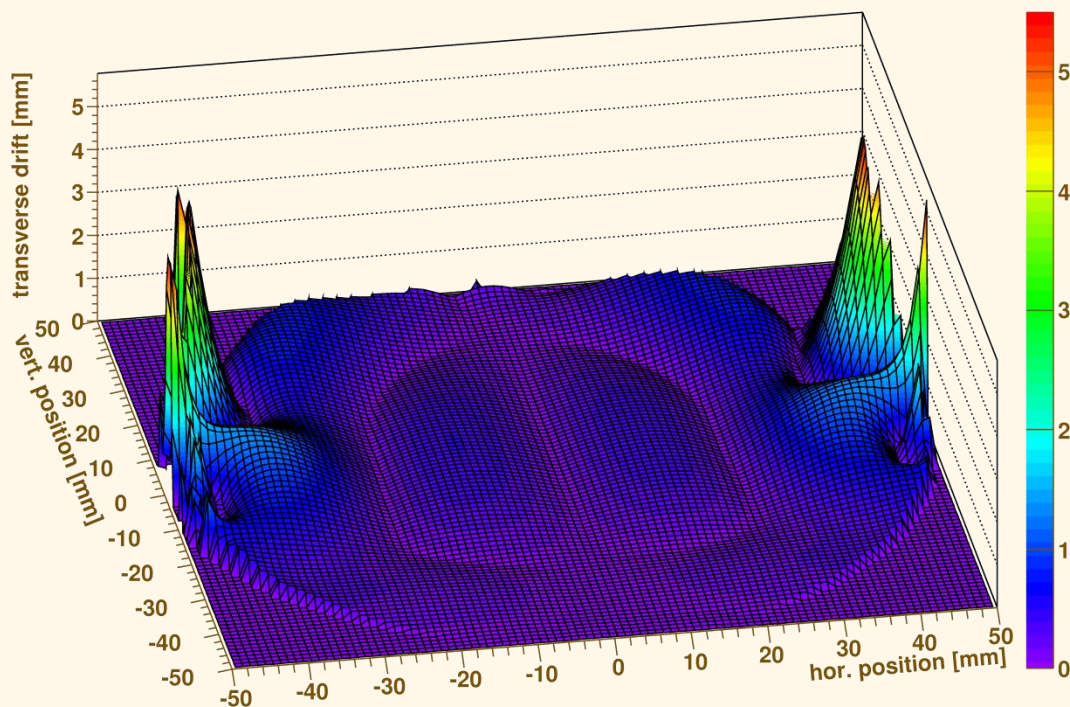
With space charge of 125 mA:

Displacement > 5 mm



Neglecting Space Charge Effect!

Simulation of the Transverse Ion Drift in the el. Field

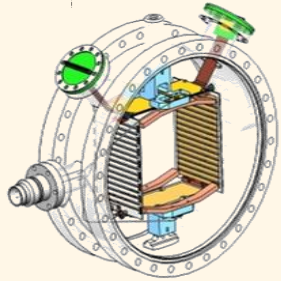
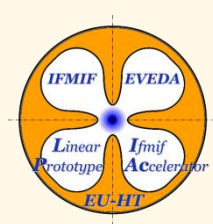


Particle Tracking:

Transverse displacement during ion drift versus starting position

Tracking w/o space charge in same scale!!!

Particle Tracking – Resulting Profile



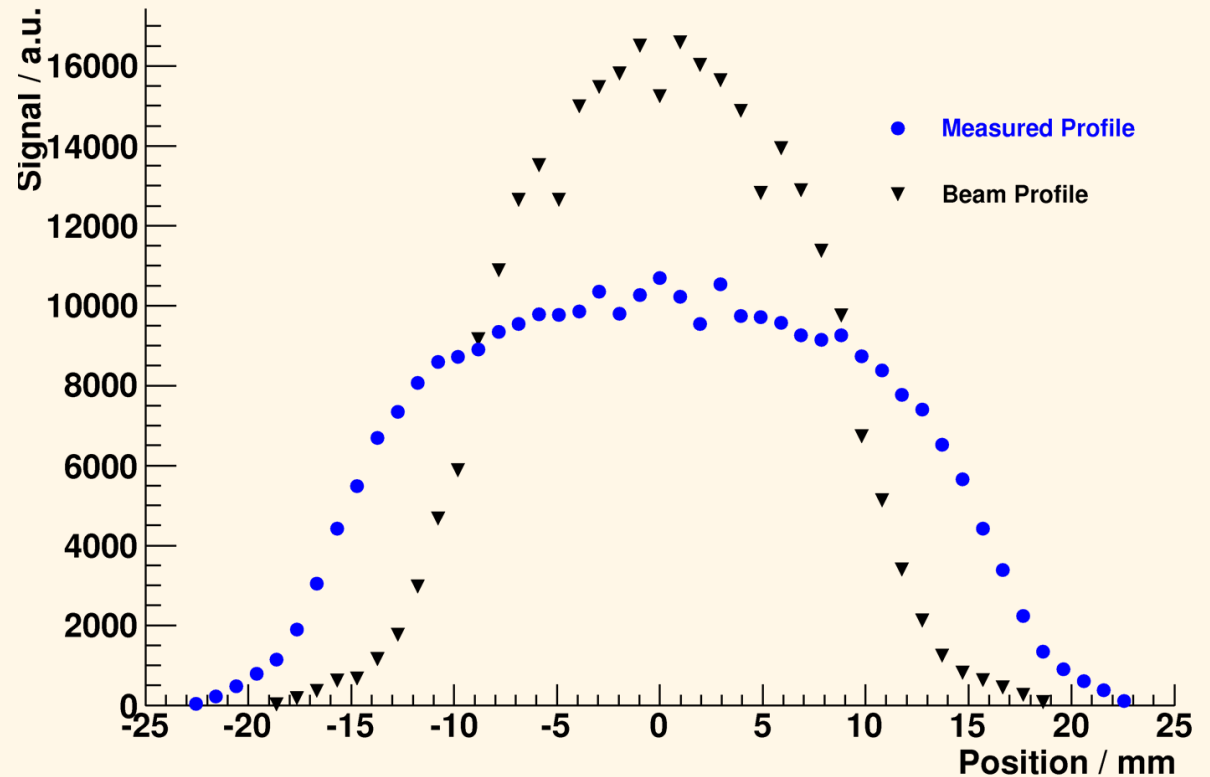
Resulting Profile:

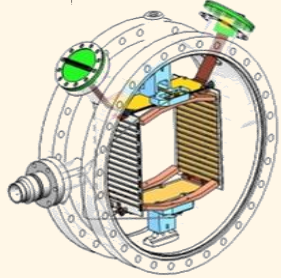
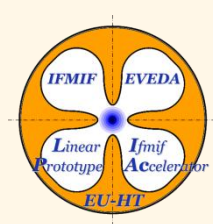
Strong Distortions due to space charge

original beam profile

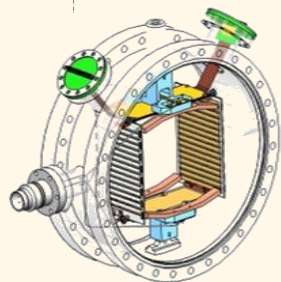
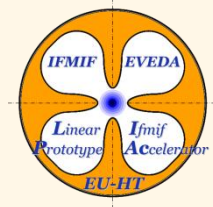
measured profile
(simulation)

Profile at asymmetric 7.5 kV

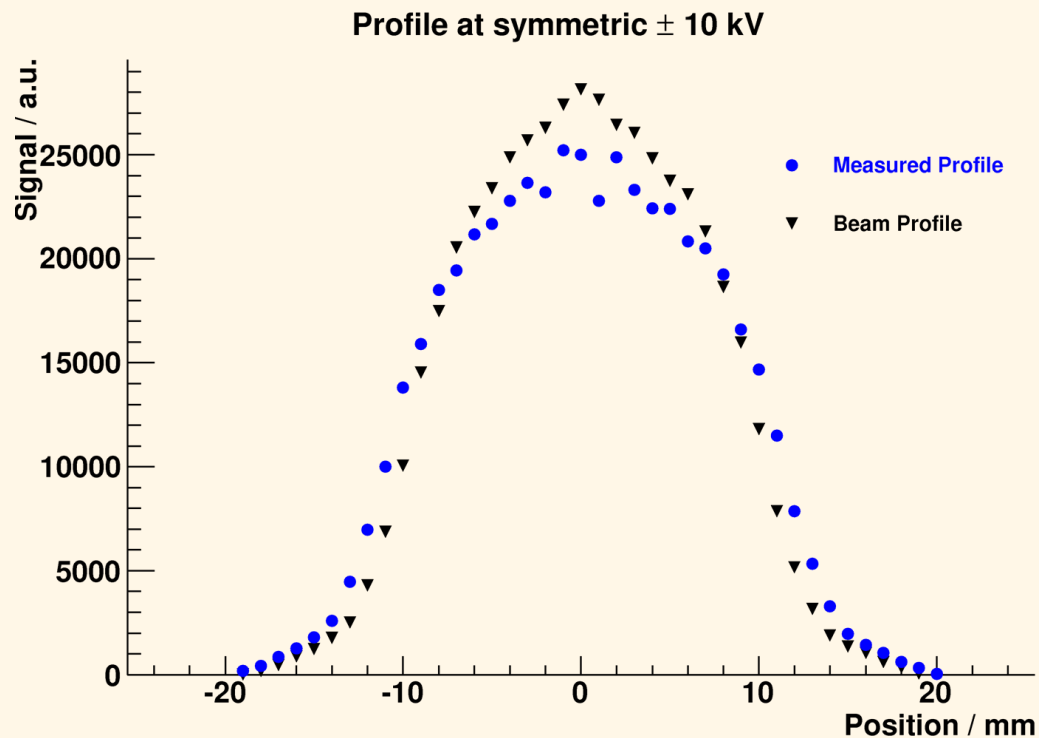




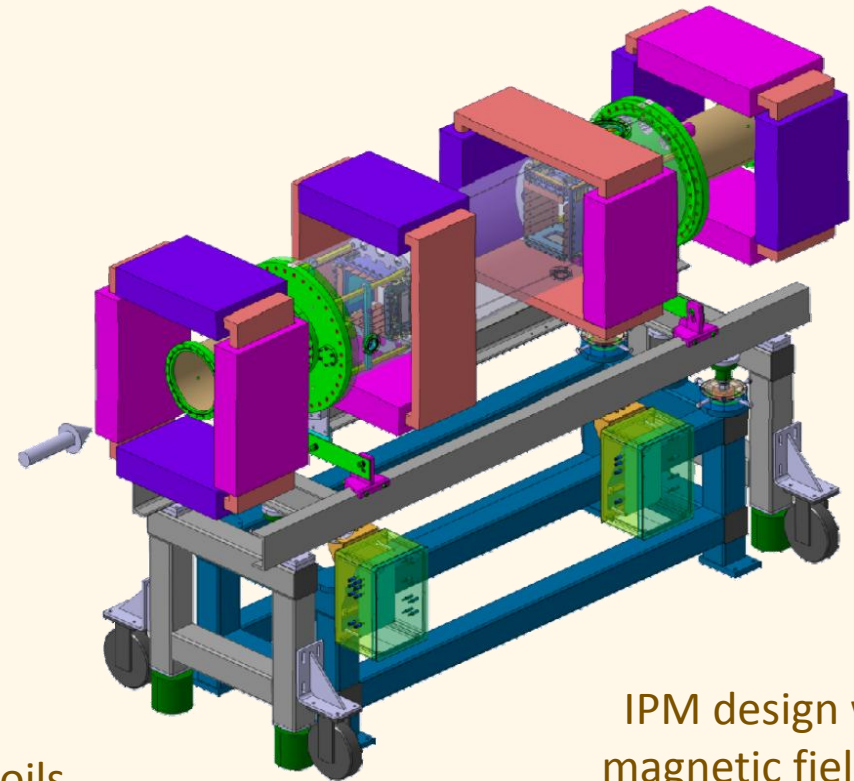
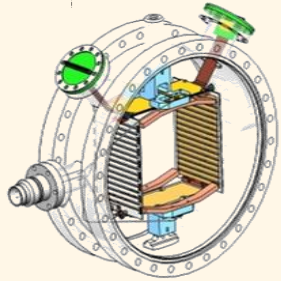
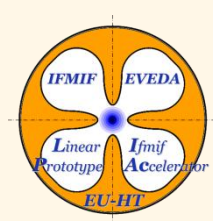
- ❖ *Increase electric field*
- ❖ *Use magnetic field guidance*
- ❖ *Apply correction algorithm*



- ❖ **Increase electric field**
 - ❖ Just minimizing effects
 - ❖ Limited voltage applicable
- ❖ **Use magnetic field guidance**
- ❖ **Apply correction algorithm**



Electric field generated by ± 10 kV instead of 7.5 kV



IPM design with magnetic field by Tino Giacomini, GSI

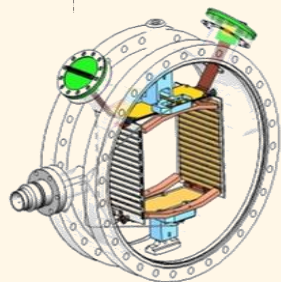
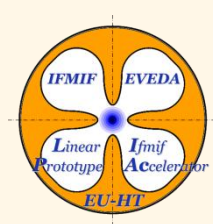
❖ *Increase electric field*

- ❖ Just minimizing effects
- ❖ Limited voltage applicable

❖ *Use magnetic field guidance*

- ❖ Space consuming due to:
 - ❖ Magnetic field compensation coils
 - ❖ Higher demands on electric field uniformity

❖ *Apply correction algorithm*



❖ Increase electric field

- ❖ Just minimizing effects
- ❖ Limited voltage applicable

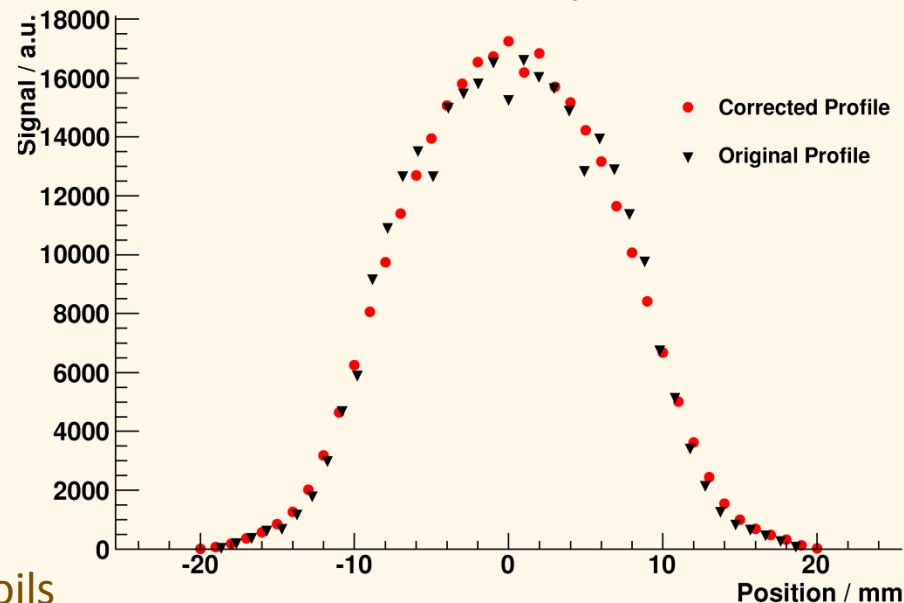
❖ Use magnetic field guidance

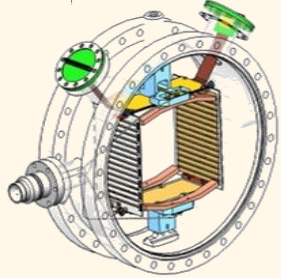
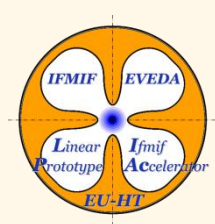
- ❖ Space consuming due to:
 - ❖ Magnetic field compensation coils
 - ❖ Higher demands on electric field uniformity

❖ Apply correction algorithm

- ❖ Risk of distortions in case of malfunctioning

Corrected Profile at asymmetric 7.5 kV

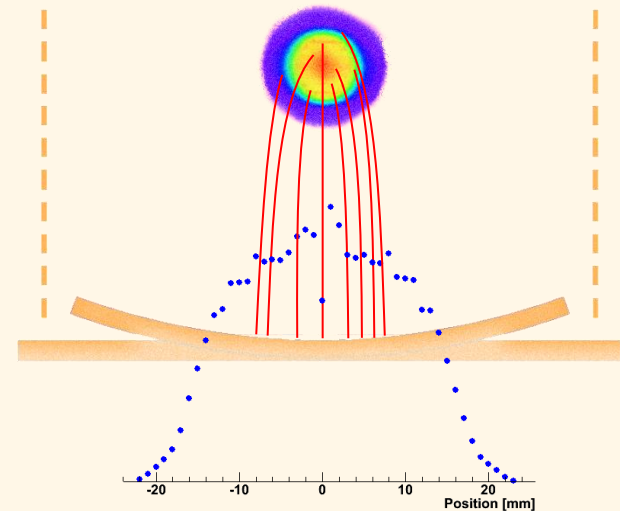
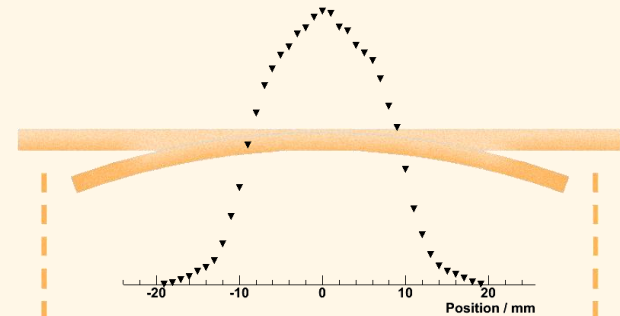




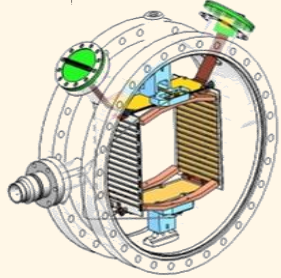
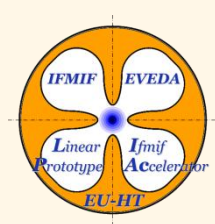
Idea:

- ❖ Calculate space charge force
- ❖ Determine ion displacement at each position
- ❖ Correct the profile

beam profile (x,y)



measured profile x'



Idea:

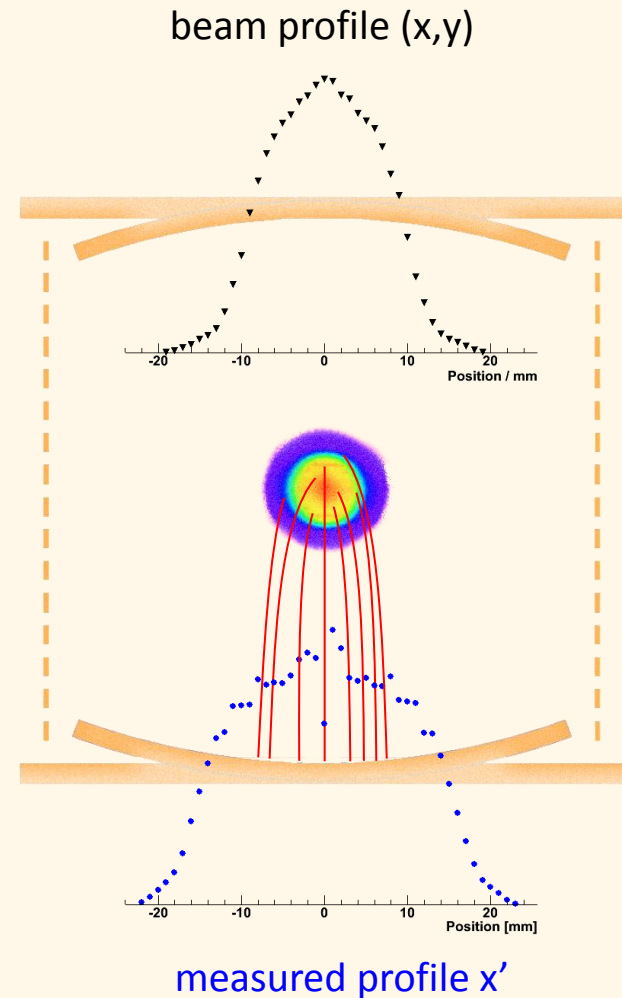
- ❖ Calculate space charge force
- ❖ Determine ion displacement at each position
- ❖ Correct the profile

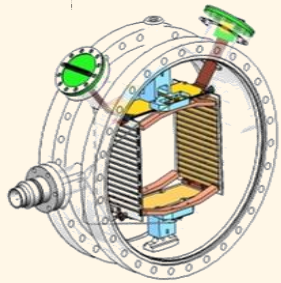
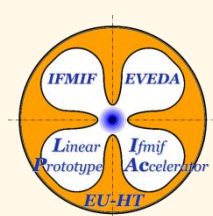
Problem:

Beam particle distribution required to calculate space charge force

Approach:

Assume *beam distribution*....





Idea:

- ❖ Calculate space charge force
- ❖ Determine ion displacement at each position
- ❖ Correct the profile

Problem:

Beam particle distribution required to calculate space charge force

Approach:

Assume *beam distribution*....

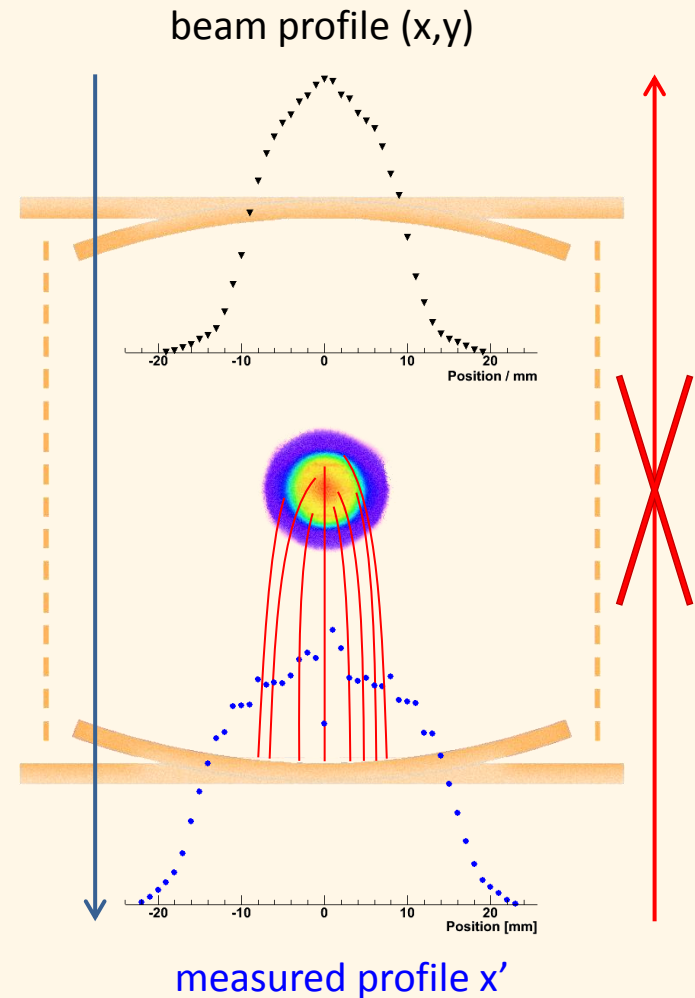
Problem:

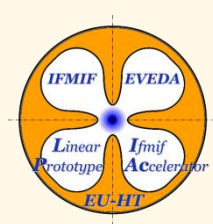
No bijective mapping between (x,y) and x'

Approach:

Apply statistics: $g(x') = \sum p_{x'}(x,y) \cdot (x,y)$

$p_{x'}(x,y)$ is given by *beam distribution*....

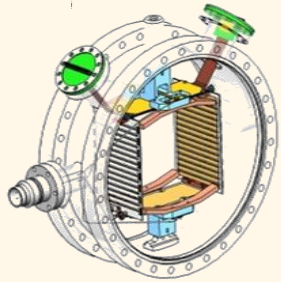




How to find the proper beam distribution?

Idea:

Vary test distribution until self-consistent solution is found!

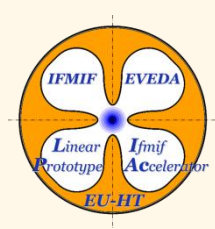


Possible criteria for self-consistency:

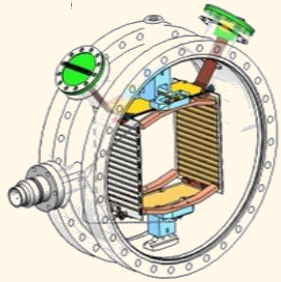
❖ *RMS (2. distribution moment)*

→ Gauss

→ strong distortions for non-Gaussian beams ☹️☹️☹️



How to find the proper beam distribution?

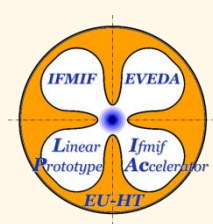


Idea:

Vary test distribution until self-consistent solution is found!

Possible criteria for self-consistency:

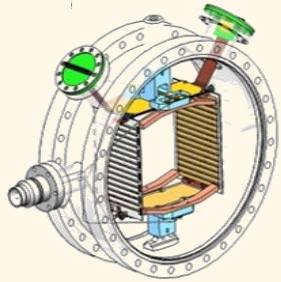
- ❖ Beam position (1. distribution moment)
- ❖ *RMS* (2. distribution moment)



How to find the proper beam distribution?

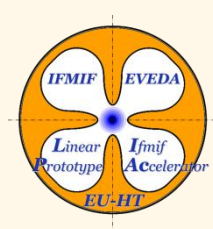
Idea:

Vary test distribution until self-consistent solution is found!

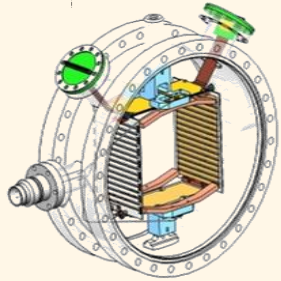


Possible criteria for self-consistency:

- ❖ ~~Beam position (1. distribution moment)~~ **unaffected by space charge**
- ❖ *RMS (2. distribution moment)*
- ❖ *Skewness (3. distribution moment)*



How to find the proper beam distribution?



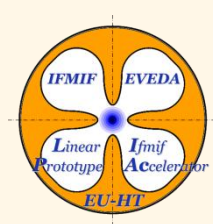
Idea:

Vary test distribution until self-consistent solution is found!

Possible criteria for self-consistency:

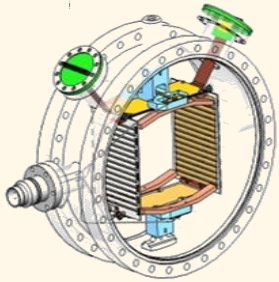
- ❖ ~~Beam position (1. distribution moment)~~ unaffected by space charge
- ❖ *RMS (2. distribution moment)* 😊😊😊
- ❖ ~~Skewness (3. distribution moment)~~ expected to be zero
- ❖ *Kurtosis (4. distribution moment)* 😊😊😊

→ two degrees of freedom!



What could be a proper test distribution?

Candidate for test distribution: Generalized Gaussian



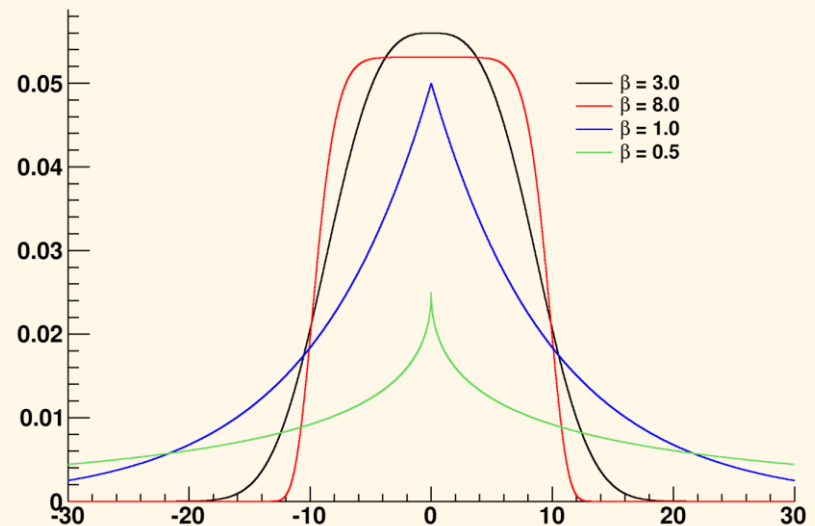
$$p_{\alpha,\beta,\mu}(x) = \frac{\beta}{2\alpha\Gamma(1/\beta)} e^{-\left(\frac{|x-\mu|}{\alpha}\right)^\beta}$$

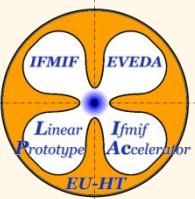
μ given by profile center

→ two degrees of freedom!

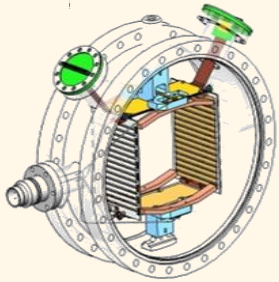
Cover any shape ranging from peaked Gaussian to rectangular distributions!

Generalized Gaussian Distributions

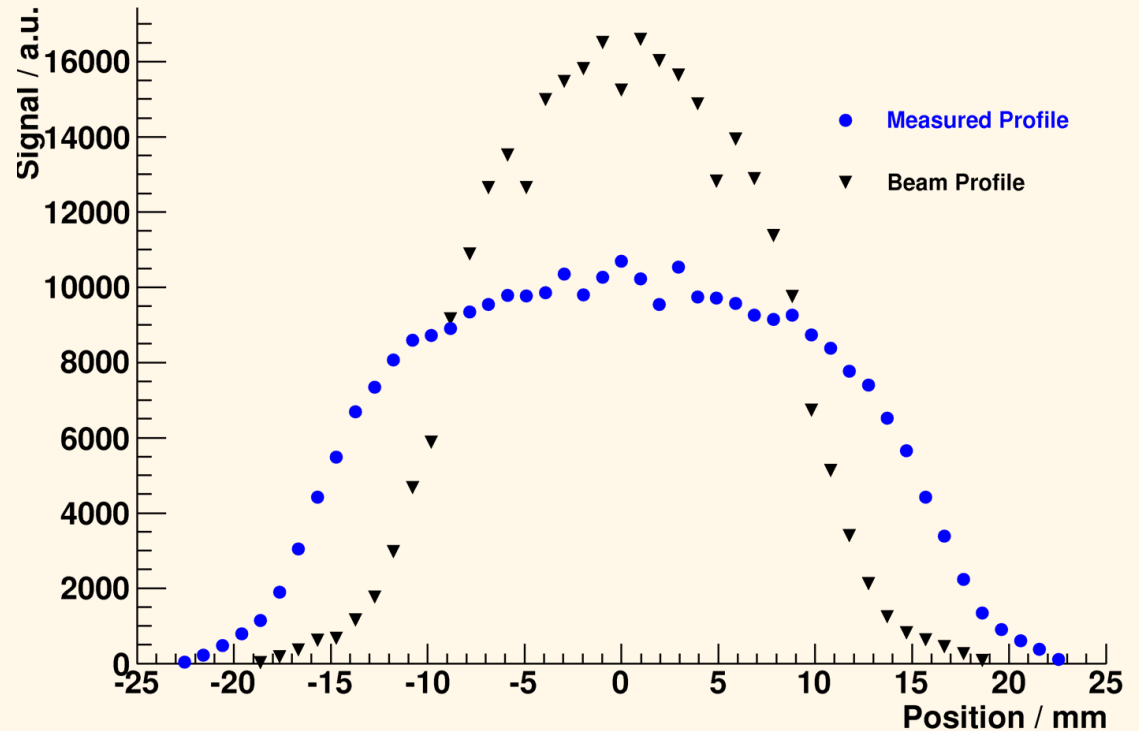


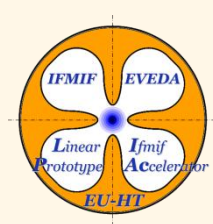


Simulation beam profile measurement:

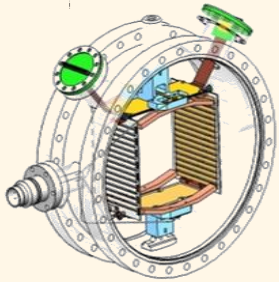


Profile at asymmetric 7.5 kV





Example of a self-consistent solution:



Parameters of test distribution:

RMS: 6.30 mm

Kurtosis: -0.50

Consistent with:

RMS: 6.38 mm

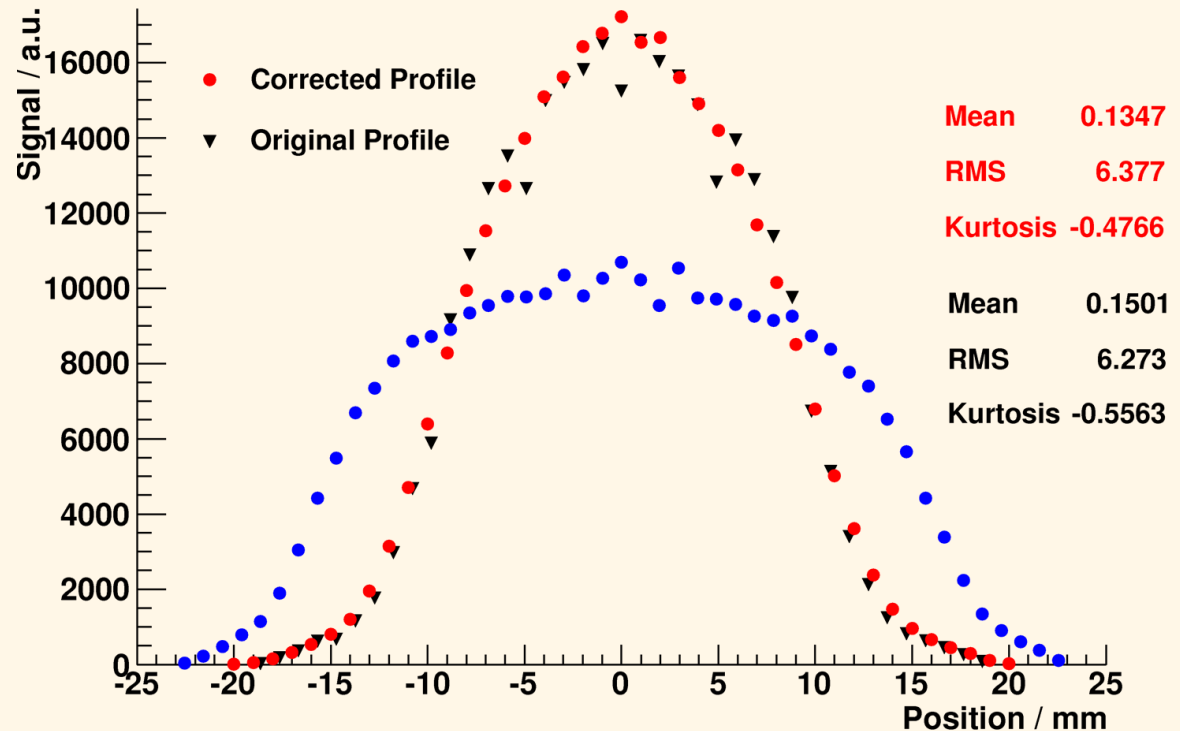
Kurtosis: -0.48

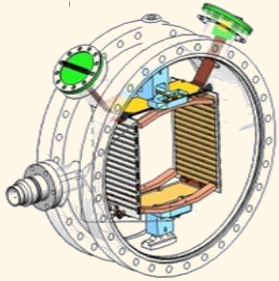
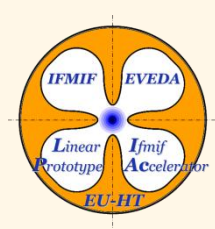
Original beam profile:

RMS: 6.27 mm

Kurtosis: -0.56

Self-Consistent Solution



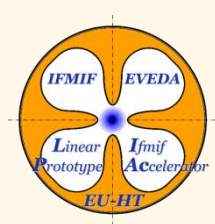


Advantages:

- ❖ Good correction results according to simulations
- ❖ Generalized Gaussians grant wide range of possible profile shapes
- ❖ Cheap - no additional hardware components required
- ❖ Option to correct for other well-known distortions

Disadvantages:

- ❖ Still in a very preliminary phase!
- ❖ Not yet practically tested!
- ❖ No correction possible for profiles that cannot be approximated by generalized Gaussians!



Conclusion

- ❖ IPM works well at low charge density beams
- ❖ IPM designed to withstand high radiation background

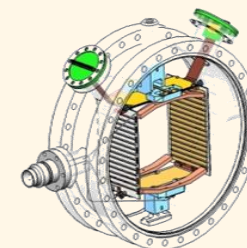
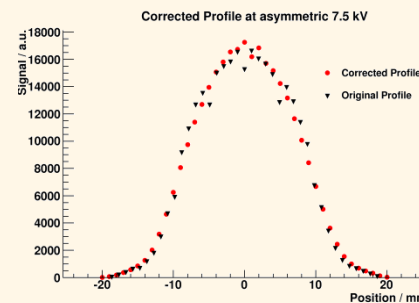
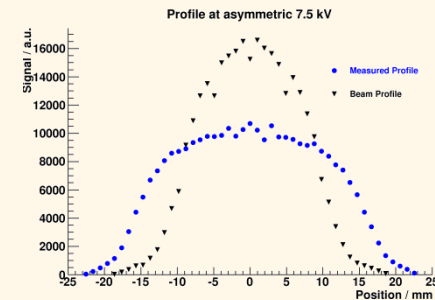
- ❖ Three options for space charge compensation:

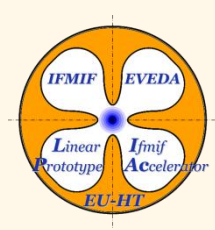
- ❖ Magnetic field
- ❖ Increased electric field
- ❖ Correction algorithm

- ❖ Magnetic field solution hardly feasible due to lack of space

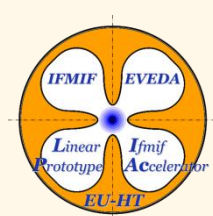
- ❖ Proposed Solution:

Correction algorithm with increased electric field to reduce effects of potential algorithm failure

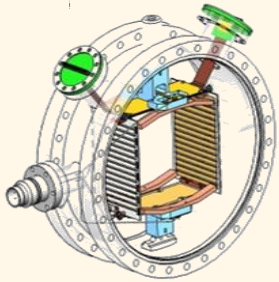




Backups



Example of a not self-consistent solution:



Parameters of test distribution:

RMS: 8.72 mm

Kurtosis: -0.81

Not consistent with:

RMS: 7.15 mm

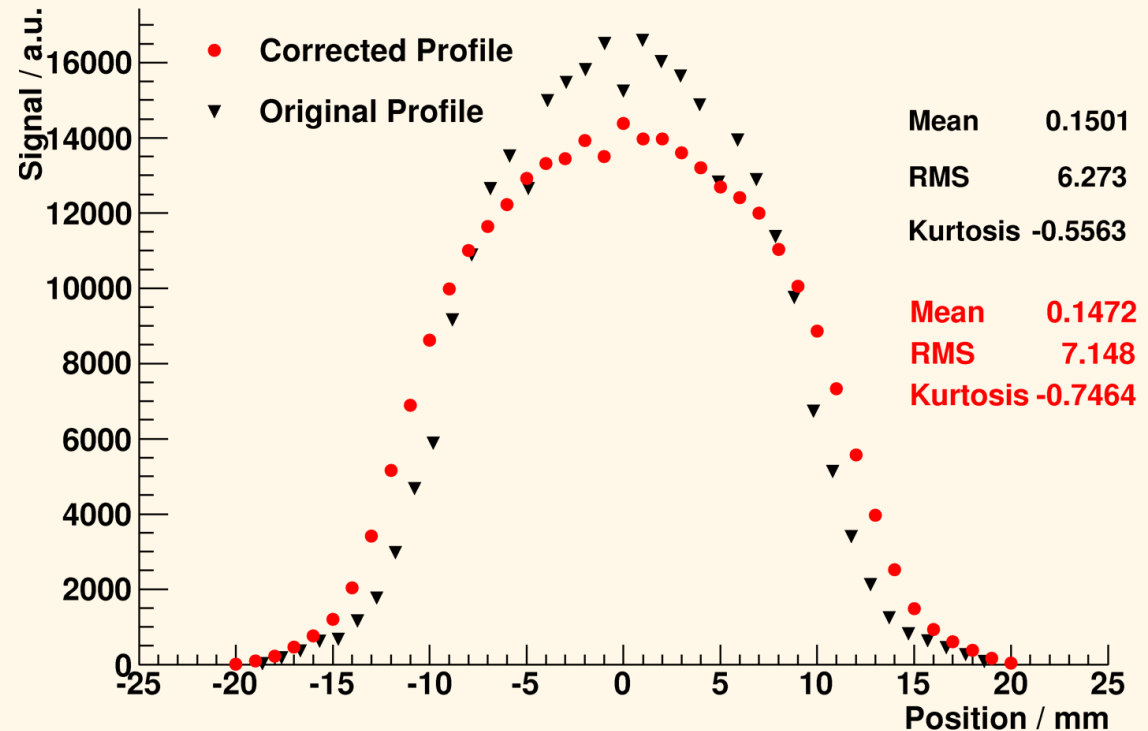
Kurtosis: -0.75

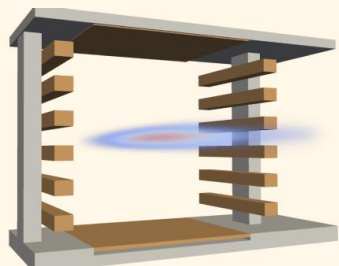
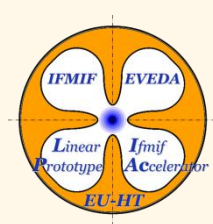
Original beam profile:

RMS: 6.27 mm

Kurtosis: -0.56

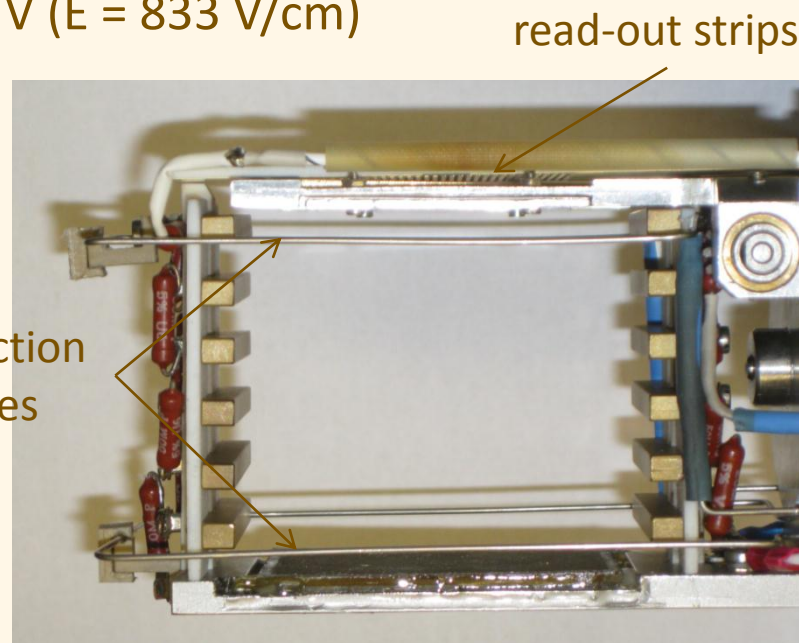
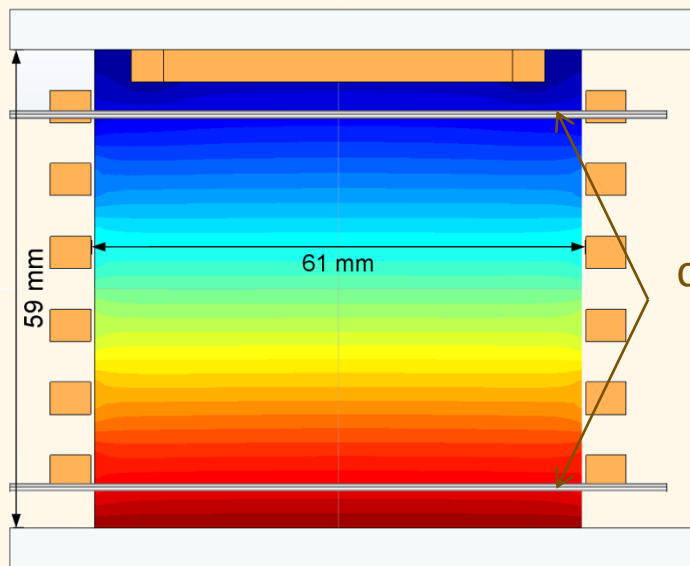
Not Self-Consistently Corrected Profile



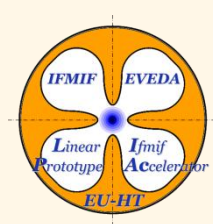


IPM Prototype Design

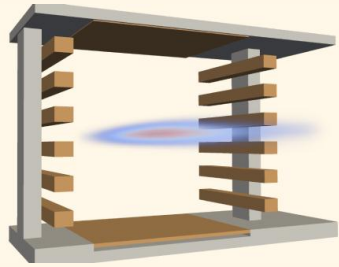
- ❖ Charge collected on 32 strips with 1.25 mm pitch
- ❖ Uniform electric field required to conserve beam profile
- ❖ Prototype designed based on FEM E-field simulations*
- ❖ Internal dimensions: 61 mm x 59 mm x 40 mm
- ❖ Voltage applied: 5000 V ($E = 833$ V/cm)



*Lorentz-E Particle Trajectory Solver Copyright © 1998 - 2010 Integrated Engineering Software Sales Inc.

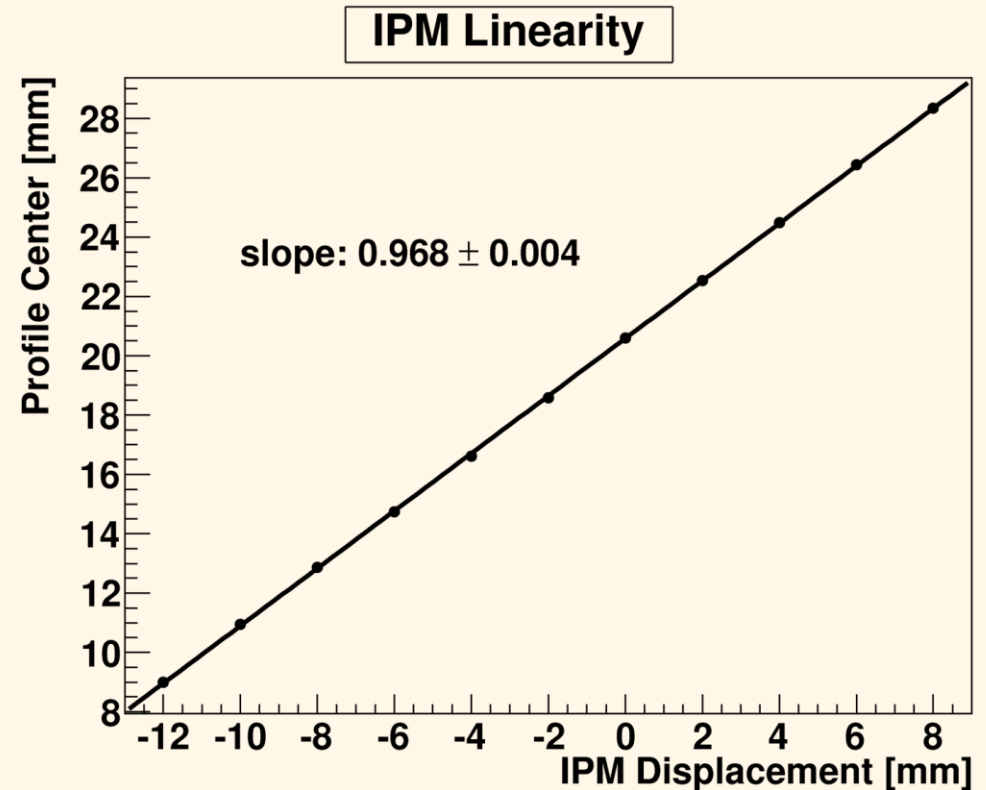


Field Uniformity Test

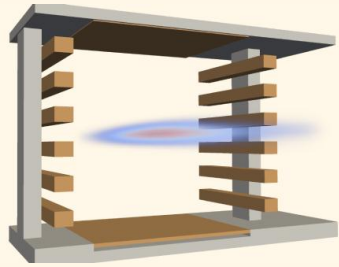
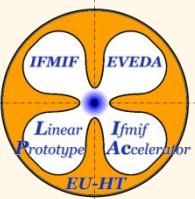


- ❖ Move IPM in 2 mm steps perpendicular to the beam
- ❖ Plot profile center versus IPM position
- ❖ Linear response over all active area

Good field uniformity

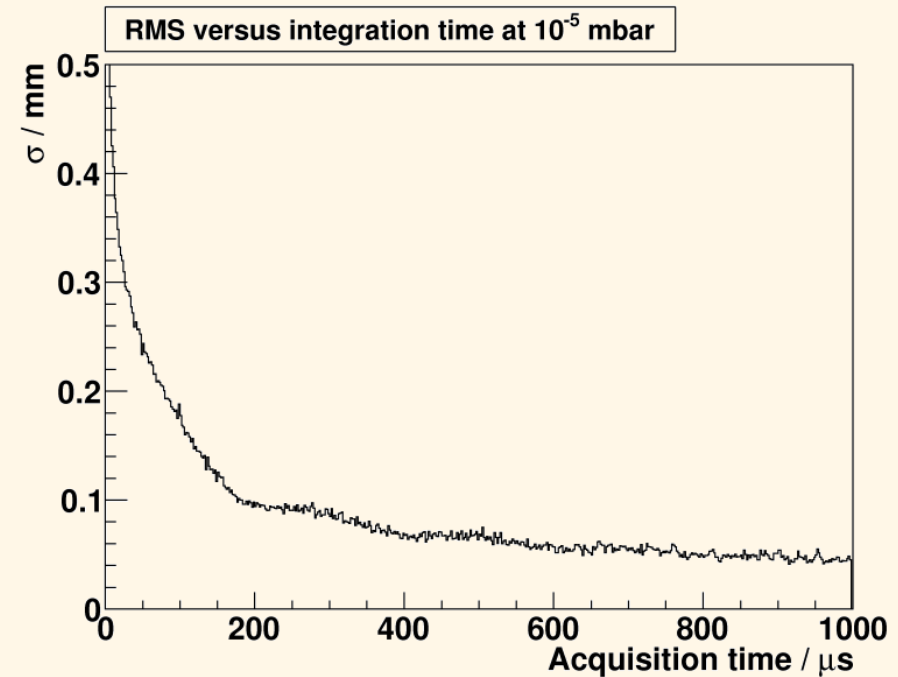


Beam: 30 μ A Ca¹⁰⁺

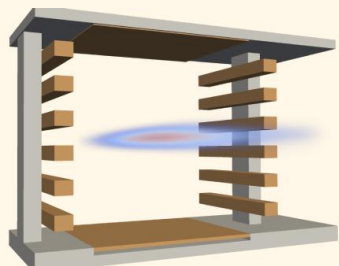
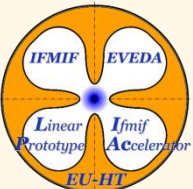


Position Resolution

- ❖ Fluctuation of beam center versus data acquisition time
- ❖ $120 \mu\text{A Xe}^{21+}$, 10^{-5} mbar N_2
- ❖ Plateau of $< 100 \mu\text{m}$ at $\sim 1\text{kHz}$



Beam: 1 mA Xe^{21+}



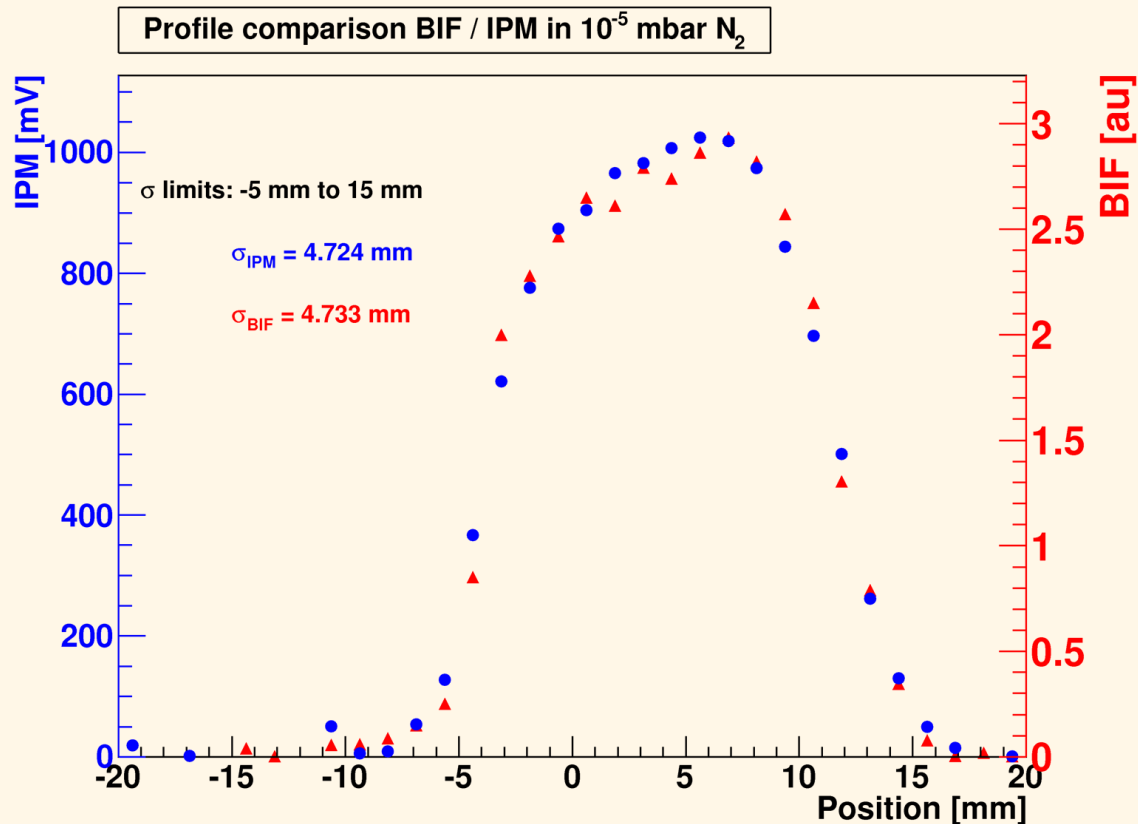
10^{-5} mbar N_2

BIF: Beam Induced
Fluorescence

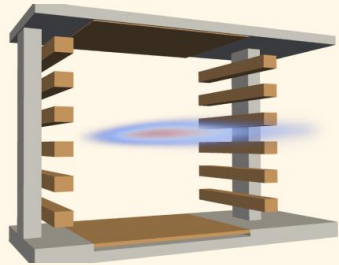
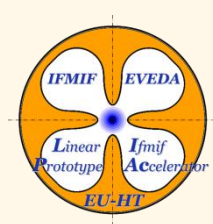
BIF Monitor based on
light emitted by atoms
excited by the beam

BIF profiles acquired by
Frank Becker, GSI

BIF Comparison

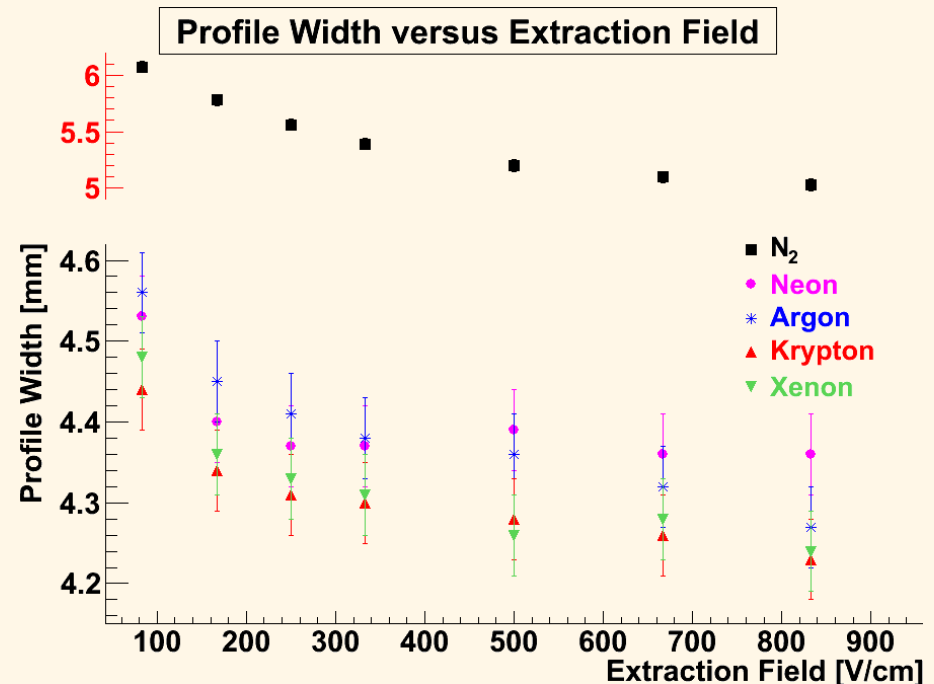


Beam: 1 mA Xe^{21+}



Electric Field Strength

- ❖ Profile width decreases with higher extraction fields
- ❖ Plateau at a few kV
- ❖ Effect stronger for molecular N_2 than for atomic noble gases



E-field dominant at 500 - 1000 V/cm

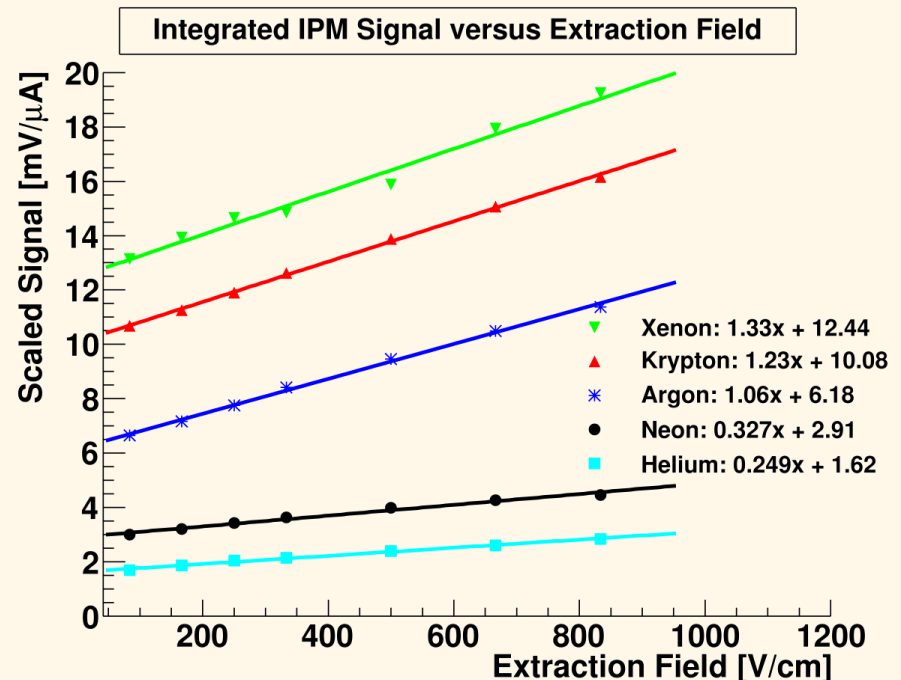
Beam: 1 mA Xe^{21+}

Signal Amplification

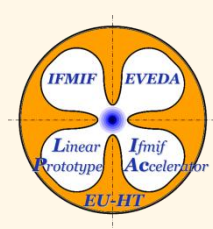
- ❖ Total strip current plotted versus extraction voltage
- ❖ Signal rises linearly

Hypothesis: Secondary electron emission during ion collection

$$\text{❖ } |\vec{E}| \propto E_{KIN} \propto SEM$$



Beam: 1 mA Xe²¹⁺



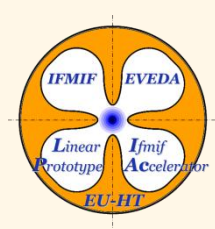
Secondary Electron Yield Comparison

	Magnuson ¹	Carlston ²	Zalm ³	Baragiola ^{4,5}	IPM
He	---	---	---	0.39	1.28
Ne	0.25	0.3	0.35	---	0.92
Ar	0.21	0.33	0.29	0.28	1.01
Kr	0.2	0.3	0.29	0.25	0.69
Xe	0.14	0.2	0.19	---	0.53

Secondary Electron Emission from IPM measurements and literature

Oxidation layer on read-out strips may increase SEE yield

1. **Magnuson, et al.** "Electron ejection from metals due to 1- to 10-keV noble gas ion bombardment. I. Polycrystalline Materials", 1963, Physical Review, Vol. 129, pp. 2403-2409
2. **Carlston, et al.** "Electron ejection form single crystals due to 1- to 10-keV noble gas ion bombardment", 1965, Physical Review, Vol. 139, pp. A729-A736
3. **Zalm, P.C. and Beckers, L.J.** "Ion-induced secondary electron emission from copper and zinc", 1985, Journal of Surface Science, Vol. 152, pp. 135-141
4. **Baragiola, et al.** "Electron emission from clean metal surfaces induced by low-energy light ions", 1979, Physical Review B, Vol. 19, pp. 121-129
5. **Baragiola, et al.** "Ion-induced electron emission from clean metals", 1979, Journal of Surface Science, Vol. 90, pp. 240-255



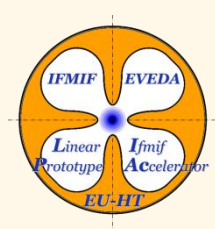
Secondary Electron Yield Comparison

	Magnuson ¹	Carlston ²	Zalm ³	Baragiola ^{4,5}	IPM
He	---	---	---	1.47	1.47
Ne	1.14	0.97	1.13	---	1.06
Ar	0.95	1.06	0.94	1.06	1.15
Kr	0.91	0.97	0.94	0.94	0.79
Xe	0.64	0.64	0.61	---	0.61

Secondary Electron Emission normalized on mean of Ne, Ar and Kr

Good agreement with literature values for normalized yields

1. **Magnuson, et al.** "Electron ejection from metals due to 1- to 10-keV noble gas ion bombardment. I. Polycrystalline Materials", 1963, Physical Review, Vol. 129, pp. 2403-2409
2. **Carlston, et al.** "Electron ejection form single crystals due to 1- to 10-keV noble gas ion bombardment", 1965, Physical Review, Vol. 139, pp. A729-A736
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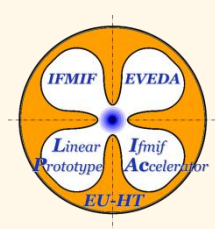
High Current Test

IPHI: Injecteur de Protons à Haute Intensité ($I < 100$ mA; $E < 95$ keV)

- ❖ Test at IPHI source
 - ❖ cw or pulsed
 - ❖ Low energy \Rightarrow high ionization cross section
 - ❖ No collimation \Rightarrow IPM is irradiated by beam

- ❖ IPM operational up to 10 mA cw (I_{ioniz} comparable to LIPAc)
 - ❖ For $I > 10$ mA: tripping power supply probably due to primary particle bombardment

- ❖ IPM tested up to 20 mA in 10 % duty cycle



lowest current measurable at IFMIF:

- ❖ measurable for $30 \mu\text{A } ^{48}\text{Ca}^{10+}$ at $1.4 \cdot 10^{-6}$ mbar
- ❖ Z^2 dependence of ionization cross section:

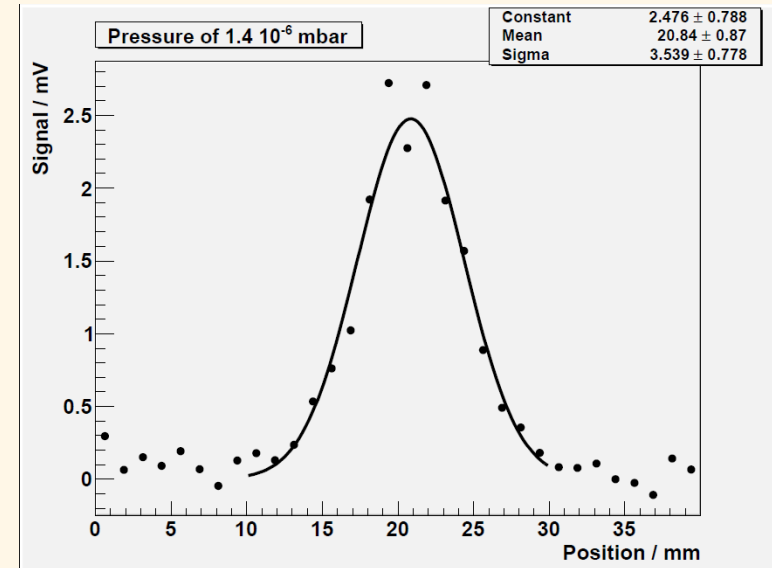
$$30 \mu\text{A } ^{48}\text{Ca}^{10+} \Leftrightarrow 300 \mu\text{A } \text{D}^+$$

- ❖ pressure scaling:

$$300 \mu\text{A} \cdot (1.4 \cdot 10^{-6} \text{ mbar} / 10^{-8} \text{ mbar}) = 42 \text{ mA at } 10^{-8} \text{ mbar,}$$

or

$$300 \mu\text{A} \cdot (1.4 \cdot 10^{-6} \text{ mbar} / 10^{-7} \text{ mbar}) = 4.2 \text{ mA at } 10^{-7} \text{ mbar}$$



Data Readout

Front-End (FE) electronics:

- ❖ FE electronics mounted on the beam pipe
 - ❖ Transimpedance card / logarithmic card:
 - ❖ Continuous multiplexed output every $\approx 2 \mu\text{s}$
 - ❖ Integrating card:
 - ❖ Integration time between $81 \mu\text{s}$ and 64ms - or even more...

Data Acquisition:

- ❖ Acqiris Card:
 - ❖ 8 bit ADC
 - ❖ 1 GHz sampling rate with 2MB memory depth
 - ❖ 2133 acquisitions per profile – up to 800 profiles per data transfer

